

EVO TARGE Nozzle

OPTIMA's Patented EVO TARGE is a high volume 4" dual flow, heat suppressing nozzle designed for offshore and onshore well testing and clean-up operations. The EVO TARGE Nozzle produces a solid water wall and an atomised fog screen with a diameter of up to 55ft.

The EVO TARGE Nozzle can be used as a standalone solution for low to medium flow rates. For higher flaring rates, it is used in conjunction with OPTIMA TARGE Rigside Cooling System.

Offshore studies have proven the EVO TARGE Nozzle can attenuate up to 70% of incident heat radiation during flaring operations.

The EVO TARGE Nozzle can be run directly from the vessel pumps or directly from OPTIMA's standalone pumps. An adjustable orifice setting allows optimisation for oil/gas well flow rates.

All EVO TARGE configurations can be pre-installed at the customers base prior to loadout or on location at the job site.



Applications

- Well Test Operations
- Flare Stack Cooling

Benefits

- Reduces heat radiation during well testing
- Preserves installation integrity
- Allows for increased well flow rates
- Personnel safety and compliance API 521

Features

- Proven heat attenuation water wall & fog barrier with up to 70% efficiency
- Dual atomisation laminar flow
- Supply from vessel Pumps or Standalone OPTIMA Pumps
- Can deliver up to 1,800usgpm

Contact us to learn more at: www.optimauk.com

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